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(12) **United States Design Patent**
Tanaka

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(54) **ION SHIELD PLATE FOR PLASMA PROCESSING DEVICE**

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(**) Term: **15 Years**

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(30) **Foreign Application Priority Data**

May 27, 2020 (JP) .... 2020-010384 D

(51) **LOC (13) Cl.** **24-02**
(52) **U.S. Cl.**
USPC **D24/224**
(58) **Field of Classification Search**
USPC ... D24/107, 110.6, 113, 129, 144, 193, 197, D24/168, 170, 187, 200, 205, 206, 224; D23/200, 213–215, 222, 223, 229, 283; D15/126, 140, 144.1; D8/352
CPC H01J 37/32082; H01J 37/32541; H01J 19/54; H01J 5/48; H01R 13/514; H01R 31/02; F21V 5/00
See application file for complete search history.

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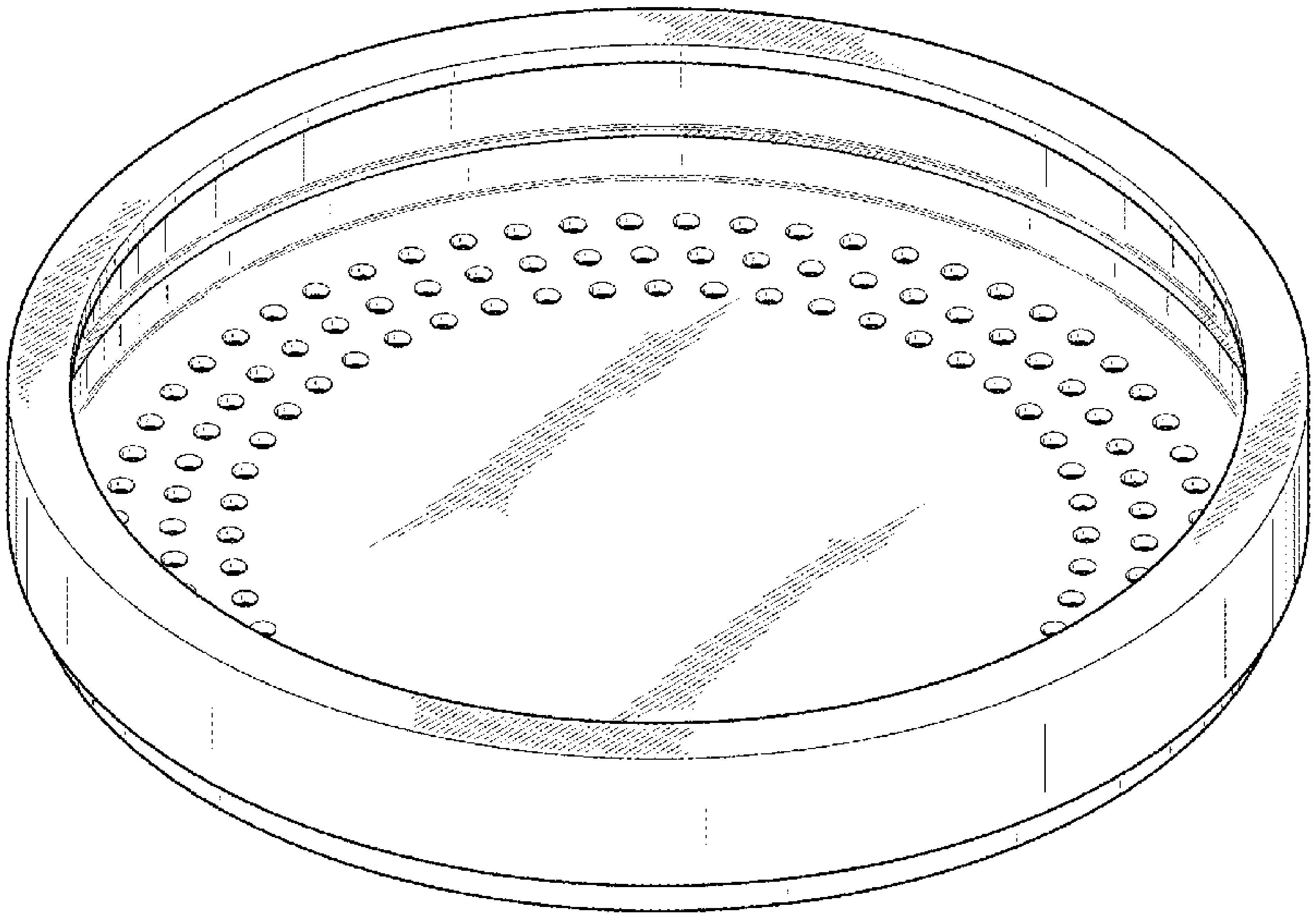
(57) **CLAIM**

The ornamental design for an ion shield plate for plasma processing apparatus, as shown and described.

DESCRIPTION

FIG. **1** is a front, top, and right side perspective view of an ion shield plate for plasma processing apparatus according to the design;
FIG. **2** is a front elevational view thereof;
FIG. **3** is a top plan view thereof;
FIG. **4** is a bottom plan view thereof;
FIG. **5** is a right side elevational view thereof;
FIG. **6** is a left side elevational view thereof;
FIG. **7** is a rear elevational view thereof;
FIG. **8** is a cross-sectional view taken along line **8-8** of FIG. **2**; and,
FIG. **9** is an enlarged view of the portion shown in box **9** in FIG. **8**.
The broken lines shown in FIGS. **8** and **9** represent the boundary of enlarged view and form no part of the claimed design.

1 Claim, 5 Drawing Sheets



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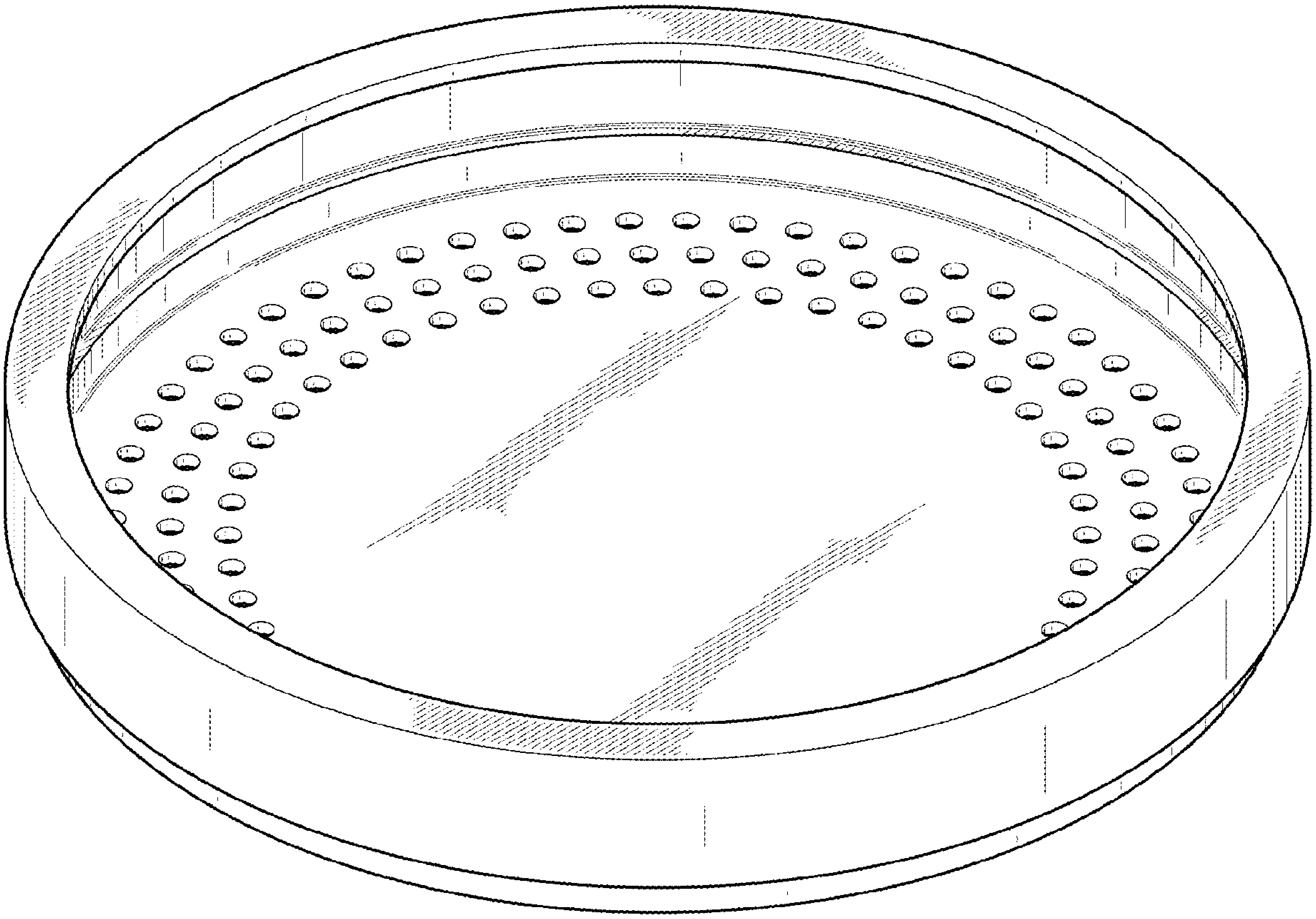

FIG. 1

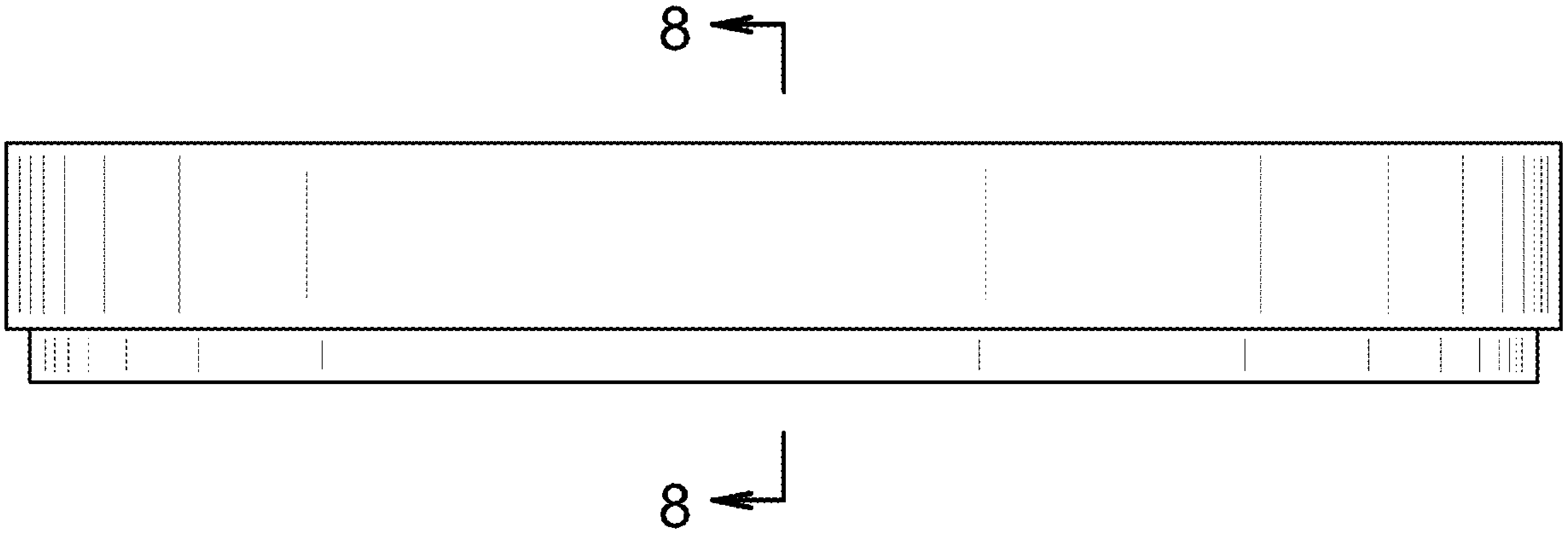

FIG. 2

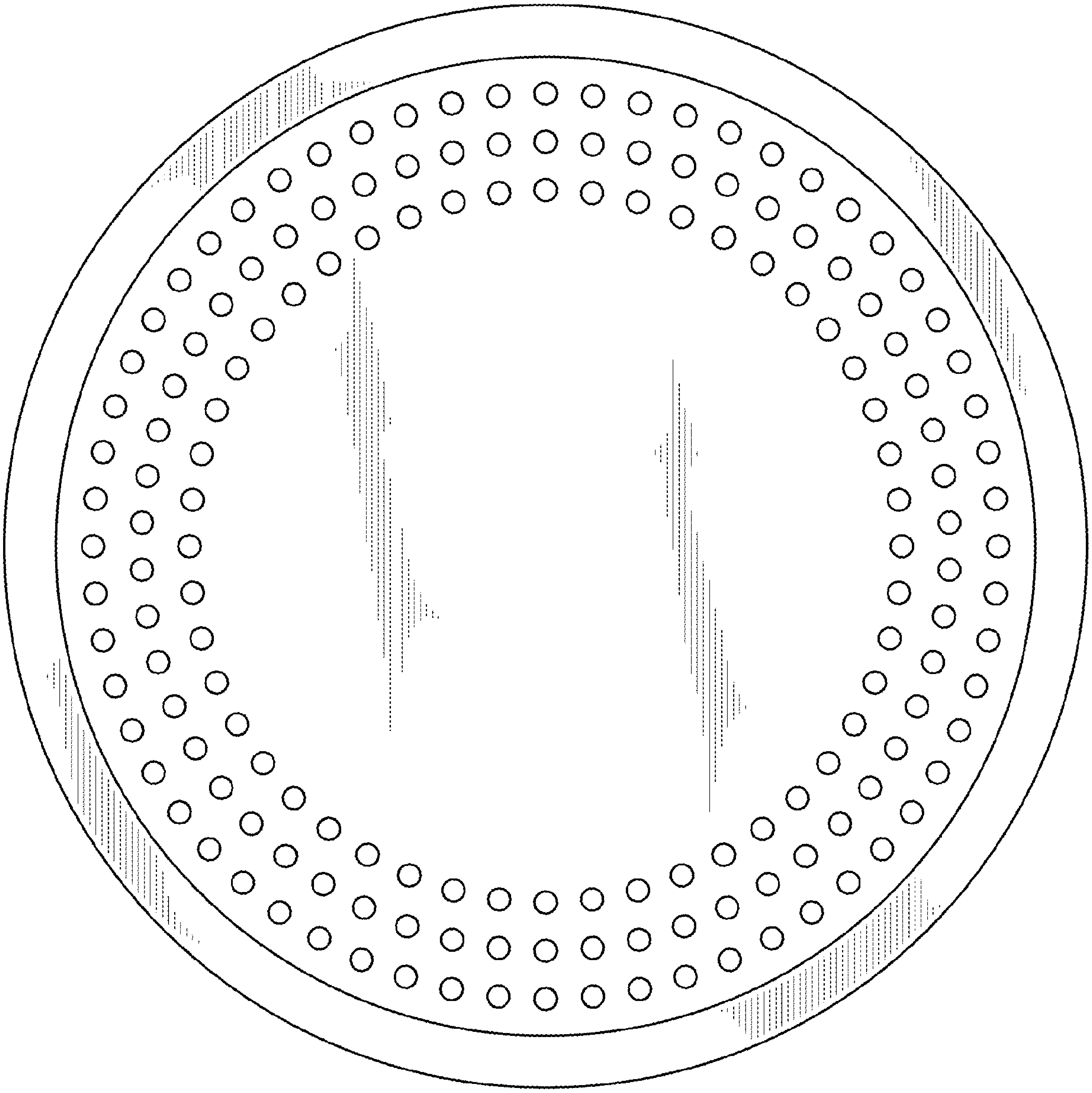

FIG. 3

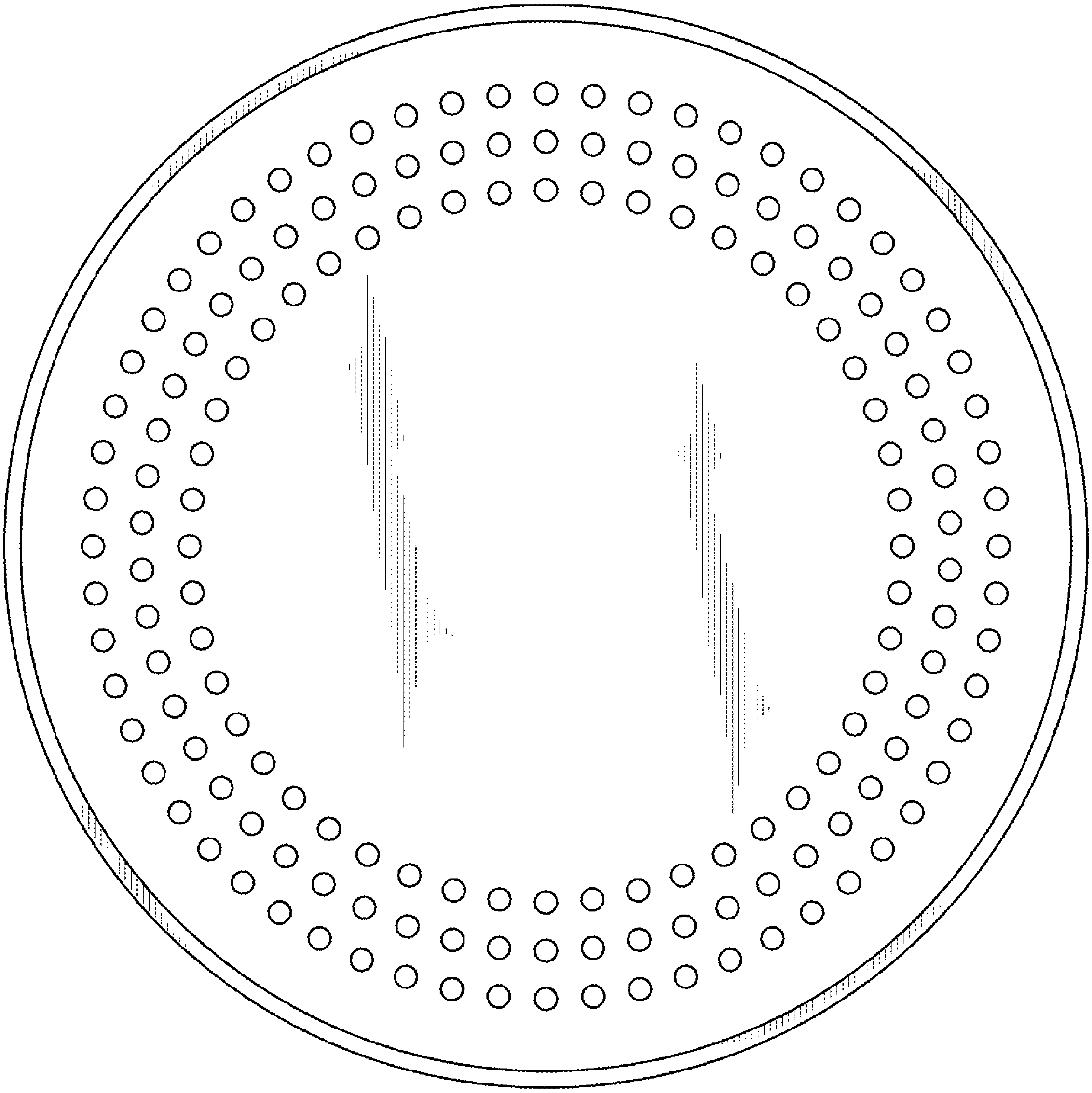

FIG. 4

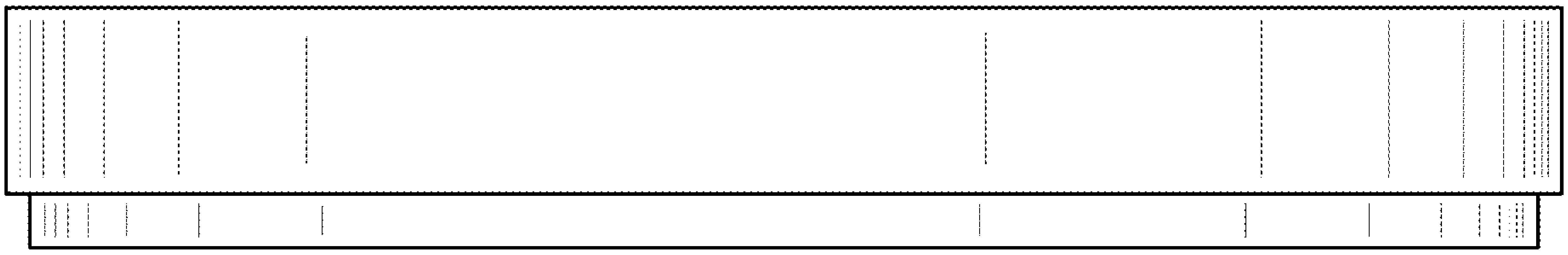

FIG. 5

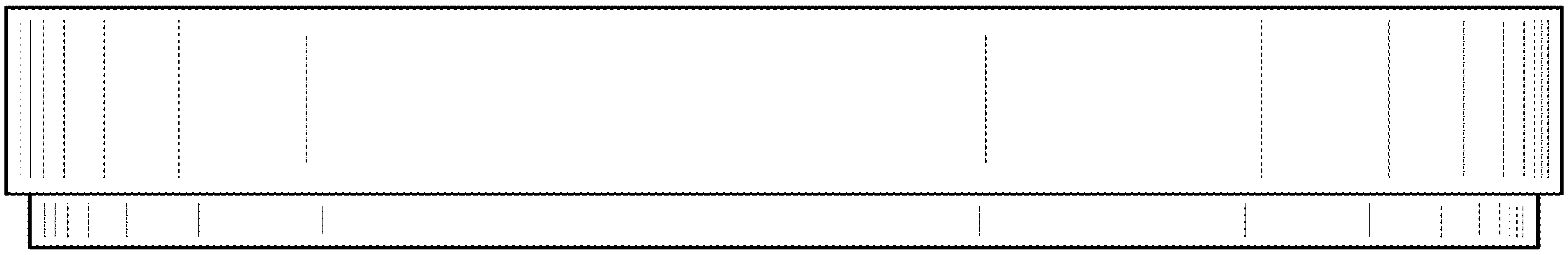

FIG. 6

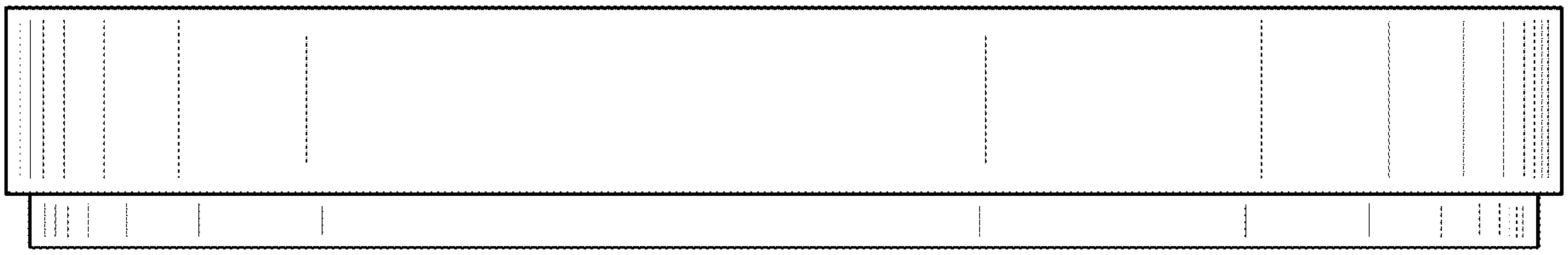

FIG. 7

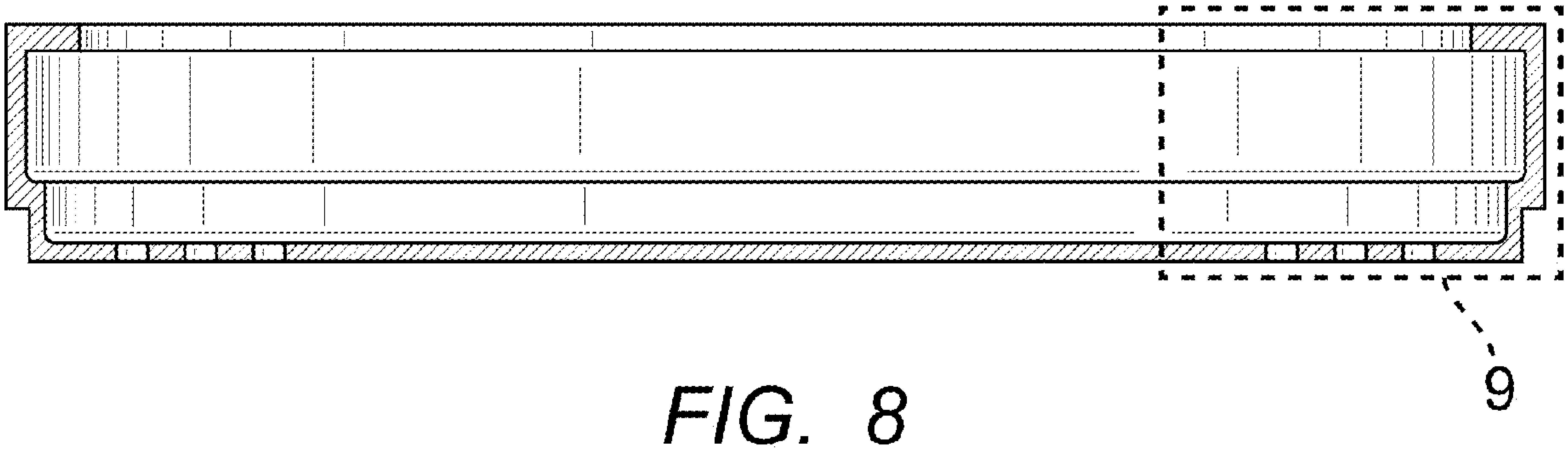

FIG. 8

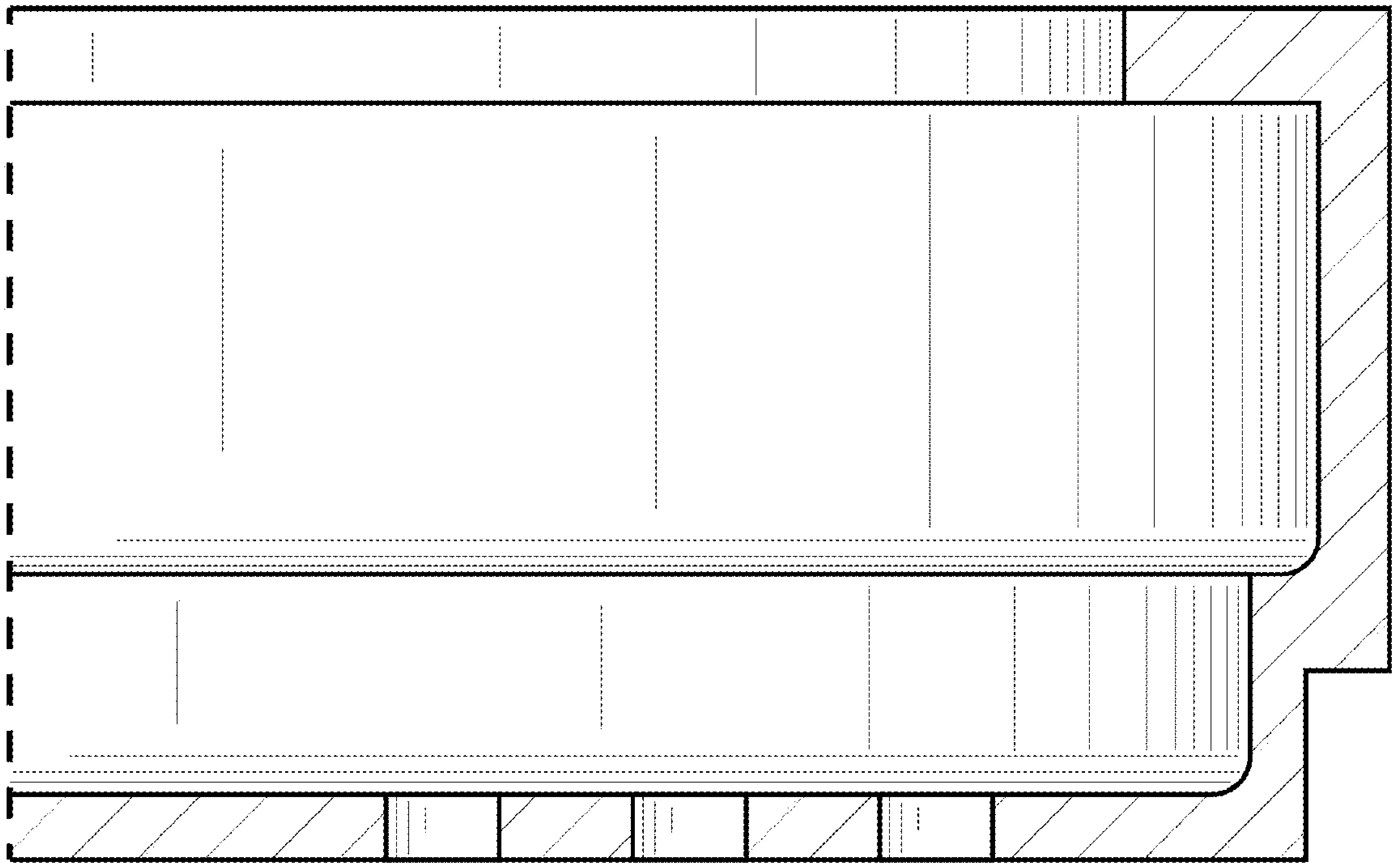

FIG. 9